



162162



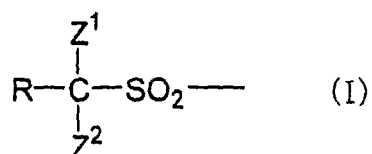
G00002

TITLE OF THE INVENTION

ACID GENERATOR, SULFONIC ACID, SULFONIC ACID DERIVATIVES AND
RADIATION-SENSITIVE RESIN COMPOSITION

ABSTRACT OF THE DISCLOSURE

A novel photoacid generator containing a structure of the following formula (I),



wherein R is a monovalent organic group with a fluorine content of 50 wt% or less, a nitro group, a cyano group, or a hydrogen atom, and Z¹ and Z² are individually a fluorine atom or a linear or branched perfluoroalkyl group having 1-10 carbon atoms, is provided. When used in a chemically amplified radiation-sensitive resin composition, the photoacid generator exhibits high transparency, comparatively high combustibility, and no bioaccumulation, and produces an acid exhibiting high acidity, high boiling point, moderately short diffusion length in the resist coating, and low dependency to mask pattern density.